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thin solid films

Contents

Synthesis and Characterization

Variations of properties of the MoS_2–LaF_3 cosputtered and MoS_2-sputtered films after storage in moist air 1
D.-Y. Yu, J.-A. Wang, J.-L.O. Yang (Lanzhou, People's Republic of China)

The mechanism of dehydrogenation of SiN_x:H films 6
T.P. Smirnova, L.V. Yakovkina (Novosibirsk, Russia)

On thermodynamic equilibria of solid BN and gas phases in the B–N–H–Cl–He system 11
A.N. Golubenko, M.L. Kosinova, V.A. Titov, A.A. Titov, F.A. Kuznetsov (Novosibirsk, Russia)

Phase evolution in boron nitride thin films prepared by a dc-gasdischarge assisted pulsed laser deposition 17
H. Xin, X. Shi, C. Lin, W. Xu, L. Zheng, S. Zou (Shanghai, China)

$CuFe_2O_4$ thin films: elaboration process, microstructural and magneto-optical properties 22
C. Despax, P. Tailhades, C. Baubet, C. Villette, A. Rousset (Toulouse, France)

The investigation of Fe–Si alloys synthesized by laser irradiation 29
Br. Petretis, A. Amulevicius, M. Balciûniene, A. Daugvila (Vilnius, Lithuania)

Morphological stability of $TiSi_2$ on polycrystalline silicon 34
J.F. Chen, L.J. Chen (Hsinchu, Taiwan)

Surface photovoltaic characterizations of porous silicon layers 40
B. Wang (Heilongjiang, People's Republic of China), D. Wang (Changchun, People's Republic of China), L. Zhang (Heilongjiang, People's Republic of China), T. Li (Changchun, People's Republic of China)

p- and n-type $CuInSe_2$ thin films grown by close-spaced vapour transport 45
G. Massé, K. Guenoun, K. Djessas (Perpignan, France), F. Guastavino (Montpellier, France)

Formation of high-quality silicon dioxide films by electron cyclotron resonance plasma oxidation and plasma-enhanced chemical vapour deposition 52
D. Landheer, J.E. Hulse, T. Quance (Ottawa, Canada)

Er-doping effects on properties of amorphous silicon films prepared by electron beam evaporations 63
R. Gan (Beijing, People's Republic of China), J. Wang (Lanzhou, People's Republic of China)

Yttria-stabilized zirconia thin films grown by r.f. magnetron sputtering from an oxide target 67
H. Tomaszewski (Warsaw, Poland), J. Haemers, N.D. Roo, J. Denul, R.D. Gryse (Ghent, Belgium)

P–d hybridization of the valence bands in chalcopyrite laser-deposited $Cu(In, Ga)Se_2$ thin films 75
V.V. Kindyak, A.S. Kindyak, V.F. Gremenok, I.A. Victorov (Belarus, Russia)

Film thickness variation in a cylindrical magnetron deposition device 78
T. Car, N. Radić (Zagreb, Croatia)

Chemical gas-phase reactions for a-Si:H and μc-Si:H deposition 83
A. Roth, F.J. Comes (Frankfurt, Germany), W. Beyer (Jülich, Germany)

Deposition of unhydrogenated diamond-like amorphous carbon films by electrolysis of organic solutions 87
H. Wang, M.-R. Shen, Z.-Y. Ning, C. Ye (Suzhou, People's Republic of China), H.-Y. Dang, C.-B. Cao, H.-S. Zhu (Beijing, People's Republic of China)

Synthesis and characterization of nanosized titanium oxide films on the (0001) α-Al_2O_3 surface 91
N.V. Dolgushev, A.A. Malkov, A.A. Malygin, S.A. Suvorov, A.V. Shchukarev (St. Petersburg, Russia), A.V. Beljaev, V.A. Bykov (Moscow, Russia)

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Surface and bulk properties of electron beam evaporated carbon films 96
J. Besold, R. Thielsch, N. Matz, C. Frenzel, R. Born, A. Möbius (Dresden, Germany)

Photoluminescent characteristics of lithium-doped zinc oxide films deposited by spray pyrolysis 103
A. Ortíz, C. Falcony, J. Hernández A., M. Garcia, J.C. Alonso (México, México)

Sol–gel-prepared ITO films for electrochromic systems 108
Y. Djaoued, V.H. Phong, S. Badilescu, P.V. Ashrit, F.E. Girouard, V.-V. Truong (Moncton, NB, Canada)

Real-time in-situ observation of PVD of *N*-vinylcarbazole with FTIR-RAS 113
M. Tamada, H. Koshikawa, H. Omichi (Takasaki, Gunma, Japan)

Characterization of indium-doped zinc oxide films deposited by pyrolytic spray with different indium compounds as dopants 117
H. Gómez, A. Maldonado, R. Asomoza, E.P. Zironi, J. Cañetas-Ortega, J. Palacios-Gómez (México, D.F., México)

Experimental and theoretical studies of coating thickness distributions obtained from high rate electron beam evaporation sources 124
O. Piot, A. Malaurie, J. Machet (Limoges, France)

Chemical vapour deposition of molybdenum carbides using C_{60} as a carbon source 133
L. Norin, U. Jansson, J.-O. Carlsson (Uppsala, Sweden)

Electronic properties of junctions between aluminum and doped poly(3,4-ethylenedioxythiophene) 138
W. Bantikassegn, O. Inganäs (Linköping, Sweden)

Young's modulus of RF-sputtered amorphous thin films in the SiO_2–Y_2O_3 system at high temperature 144
T. Shinoda, N. Soga, T. Hanada, S. Tanabe (Kyoto, Japan)

Quasiatomically flat surfaces of CdTe growth by evaporation technique 149
M. Aguilar, A.I. Oliva, R. Castro-Rodriguez, J.L. Peña (Yucatán, México)

K^+ sensors based on supported alkanethiol/phospholipid bilayers 153
L. Ding, J. Li, E. Wang, S. Dong (Changchun, Jilin, People's Republic of China)

Photoconductivity of Langmuir–Blodgett films of corbathiene 159
A. Komolov (St. Petersburg, Russia), K. Schaumburg, N. Harrit (Copenhagen, Denmark)

Elaboration and characterization of titania coatings 163
S. Ben Amor, G. Baud, J.P. Besse, M. Jacquet (Aubière, France)

Structural study on the alternating Langmuir–Blodgett films deposited with two complementary barbituric acid and melamine derivatives 170
Y. Ren, B. Zhao, X. Chai, A. Lu, S. Chen, Y. Cao, W. Yang, R. Lu, J. Duo, Y. Jiang, T. Li (Changchun, People's Republic of China)

A novel lithium conductor prepared by unbalanced magnetron r.f. sputtering 175
L.Q. Nguyen, L. Chen, V.-V. Truong (Moncton, NB, Canada)

Air pockets in thin porous platinum films studied by spectroscopic ellipsometry 179
S. Guo, E. Hedborg, I. Lundström, H. Arwin (Linköping, Sweden)

Surfaces, Interfaces and Colloidal Behaviour

Observing the breathing of silica sol–gel-derived anti-reflection optical coatings 185
M.S.W. Vong, P.A. Sermon (Uxbridge, UK)

Rapid thermal annealing effects in CdTe (111) thin films grown on Si (100) substrates by molecular beam epitaxy 196
M.S. Han, Y.S. Ryu, B.K. Song, T.W. Kang, T.W. Kim (Seoul, South Korea)

Electrochemical study of the interfacial characteristics of redox-active viologen thiol self-assembled monolayers 200
J. Li, G. Cheng, S. Dong (Changchun, People's Republic of China)

Metallurgical, Protective and Hard Layers

Relation between mechanical and structural properties of silicon-incorporated hard a-C:H films 206
A.L. Baia Neto, R.A. Santos, F.L. Freire, Jr., S.S. Camargo, Jr. (Rio de Janeiro, RJ CEP, Brazil), R. Carius, F. Finger, W. Beyer (Jülich, Germany)

Effects of r.f. bias and nitrogen flow rates on the reactive sputtering of TiAlN films 212
B.-Y. Shew, J.-L. Huang (Tainan, Taiwan), D.-F. Lii (Kaohsiung, Taiwan)

Nitriding of titanium under CW CO_2 laser radiation 220
P. Laurens, H. L'Enfant, M.C. Sainte Catherine, J.J. Bléchet (Arcueil, France), J. Amouroux (Paris, France)

Structural changes in plasma-sprayed ZrO_2 coatings after hot isostatic pressing 227
H.C. Chen, E. Pfender, J. Heberlein (Minneapolis, MN, USA)

Structure and mechanical properties of hard amorphous carbon–nitrogen films obtained by plasma decomposition of methane–ammonia mixtures 236
F.L. Freire Jr. , D.F. Franceschini (Rio de Janeiro, RJ, Brazil)

Mechanics and Nanomechanics of Thin Layers

Mechanical properties of r.f. magnetron sputtered indium tin oxide films 244
W.-F. Wu, B.-S. Chiou (Hsinchu, Taiwan)

Effect of substrate and bond coat on contact damage in zirconia-based plasma-sprayed coatings 251
S. Wuttiphan, A. Pajares, B.R. Lawn (Gaithersburg, MD, USA), C.C. Berndt (Stony Brook, NY, USA)

Formation and adhesion of hot filament CVD diamond films on titanium substrates 261
X.L. Peng, T.W. Clyne (Cambridge, UK)

Electronics, Optics and Opto-electronics

Electric field dependence of optical absorption in UV and visible region in PVA film 270
D.-H. Wang (Beijing, China)

Preparation and characterization of CdS/CdTe thin film solar cells 272
J. Toušková, D. Kindl, J. Toušek (Prague, Czech Republic)

Langmuir-Blodgett, Biological and Related Films

The effects of detected gases on spectroscopic properties of phthalocyanine Langmuir–Blodgett films 277
D.P. Jiang, L.G. Zhang, Y. Fan, X.G. Ren, Z.S. Guan, Y.J. Li, A.D. Lu (Changchun, People's Republic of China)

Photoinduced transformation of wild-type and D96N-mutant 4-keto-bacteriorhodopsin gelatin films 281
A.B. Druzhko, H.H. Weetall (Gaithersburg, MD, USA)

The study of correlation between the dye molecule behaviour in monolayers and their spectral properties in Langmuir–Blodgett films 285
G. Chudinova, O. Pokrovskaya, V. Barachevsky (Moscow, Russia)

Structural characterisation of sodium behenate Langmuir–Blodgett films using X-ray diffraction techniques 291
E. Milella, C. Giannini, L. Tapfer (Brindisi, Italy)

Analysis of the dynamic organization of mixed protein/fatty acid Langmuir films 295
S. Alexandre, N. Dubreuil, C. Fiol, D. Lair (Mont-Saint Aignan, France), F. Sommer, T.M. Duc (Villeurbanne, France), J.M. Valleton (Mont-Saint Aignan, France)

Maxwell displacement current due to phase transitions in liquid crystals on a water surface 299
M. Iwamoto, T. Kubota, M.R. Muhamad (Tokyo, Japan)

Condensed Matter Film Behaviour

Electrical and optical properties of thermally evaporated thin films of $(As_2S_3)_{1-x}(PbS)_x$ 303
K.L. Bhatia, M. Singh, N. Kishore (Rohtak, India)

Investigation on solid phase epitaxy of deposited SiGe film on a Si substrate 310
W.-J. Qi, B.-Z. Li, G.-B. Jiang, Z.-G. Gu, T.K. Kwok (Shanghai, People's Republic of China), R.J. Zhang, P.K. Chu (Hong Kong, Hong Kong)

The effect of growth temperature on electrical conductivity and on the structure of thin refractory metal films, grown by laser ablation deposition 315
G.M. Mikhailov, I.V. Malikov, A.V. Chernykh, V.T. Petrashov (Moscow District, Russia)

Effective conductivity of chemically deposited ZnO thin films 320
M. Robles (Cuernavaca, Morelos, Mexico), J. Tagüeña-Martínez, J.A. Del Río (Temixco, Morelos, Mexico)

Copper enrichment in Al–Cu alloys due to electropolishing and anodic oxidation 327
X. Zhou, G.E. Thompson (Manchester, UK), H. Habazaki (Sendai, Japan), K. Shimizu (Yokohoma, Japan), P. Skeldon, G.C. Wood (Manchester, UK)

Errata 333
Author Index of Volume 293 335
Subject Index of Volume 293 337

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